

## ABSTRACT OF THE DISCLOSURE

A method of using PFCs recovered from the effluent of a CVD chamber cleaning  
5 process as an influent for the cleaning process is provided which includes the steps of  
selecting a first PFC gas mixture having a first ratio of  $C_2F_6$  to  $CF_4$ , providing the first  
PFC gas mixture as the influent gas to the CVD chamber to create a CVD chamber  
effluent gas of a second PFC gas mixture having a second ratio of  $C_2F_6$  to  $CF_4$ , adding  
virgin  $C_2F_6$  or  $CF_4$  to the CVD chamber effluent gas in sufficient quantity to create a third  
10 PFC gas mixture having the first ratio of  $C_2F_6$  to  $CF_4$ , and using the third PFC gas  
mixture as the influent gas to the CVD chamber.

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